

AMENDMENTS TO THE CLAIMS

1. (withdrawn): A method for forming a light emitting diode comprising following steps:
forming a first stack;
5 forming a second reaction layer over said first stack;
forming a second stack;
forming a first reaction layer over said second stack;
holding together said first reaction layer and said second
10 reaction layer by means of a transparent adhesive
layer.
2. (withdrawn): The method of claim 1 wherein the step of
forming a first stack comprises following steps:
providing a first substrate;
15 forming a second contact layer on the first substrate;
forming a second cladding layer on the second contact
layer;
forming an emitting layer on the second cladding layer;
forming a first cladding layer on the emitting layer;
20 forming a first contact layer on the first cladding layer;
and
forming a transparent conductive layer on the first
contact layer.
- 25 3. (withdrawn): The method of claim 2 further comprising
following steps:
removing the first substrate;
etching the second contact layer, the second cladding
layer, the emitting layer, first cladding layer, and
30 the first contact layer; and
forming a first electrode on the second contact layer, and
a second electrode on the transparent conductive

layer.

4. (withdrawn): The method of claim 2 wherein the first substrate comprises at least one material selected from a group consisting of GaP, GaAs, and Ge.
5. (withdrawn): The method of claim 2 wherein the first contact layer and the second contact layer each comprise at least one material selected from a group consisting of GaP, GaAs, GaAsP, InGaP, AlGaInP, and AlGaAs.
6. (withdrawn): The method of claim 2 wherein the first cladding layer, the emitting layer, and the second cladding layer each comprise AlGaInP.
7. (withdrawn): The method of claim 2 wherein the transparent conductive layer comprises at least one material selected from a group consisting of indium tin oxide, cadmium tin oxide, antimony tin oxide, zinc oxide, zinc tin oxide, BeAu, GeAu, and Ni/Au.
8. (withdrawn): The method of claim 1 wherein the first and second reaction layers each comprise at least one material selected from a group consisting of SiNx, Ti, and Cr.
9. (withdrawn): The method of claim 1 wherein the transparent adhesive layer comprises at least one material selected from a group consisting of PI, BCB, and PFCB.
10. (withdrawn): The method of claim 1 wherein forming a second stack comprises forming a second substrate.

11. (withdrawn): The method of claim 10 wherein the second substrate comprises at least one material selected from a group consisting of SiC, Al₂O₃, glass materials, quartz, GaP, GaAsP, and AlGaAs.

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12. (withdrawn): The method of claim 1 wherein said first reaction layer and said second reaction layer are held together with the transparent adhesive layer by chemical bonds.

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13. (withdrawn): The method of claim 12 wherein the chemical bonds are hydrogen bonds or ionic bonds.

14. (original): A light emitting diode comprising:

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a first stack;

a second reaction layer formed on the first stack;

a second stack;

a first reaction layer formed on the second stack;

a transparent adhesive layer formed between the first and second reaction layers; and

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a first electrode and a second electrode formed on the first stack.

15. (original): The light emitting diode of claim 14 wherein the first stack comprises:

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a transparent conductive layer formed on the second reaction layer, the transparent conductive layer

having a first surface area and a second surface area;

a first contact layer formed on the first surface area of the transparent conductive layer;

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a first cladding layer formed on the first contact layer; an emitting layer formed on the first cladding layer;

a second cladding layer formed on the emitting layer; and
a second contact layer formed on the second cladding layer;
wherein the first electrode is formed on the second contact
layer, and the second electrode is formed on the second
5 surface area of the transparent conductive layer.

16. (original): The light emitting diode of claim 15 wherein
the first contact layer and the second contact layer each
comprise at least one material selected from a group
10 consisting of GaP, GaAs, GaAsP, InGaP, AlGaInP, and
AlGaAs.

17. (original): The light emitting diode of claim 15 wherein
the first cladding layer, the emitting layer, and the
15 second cladding layer each comprise AlGaInP.

18. (original): The light emitting diode of claim 15 wherein
the transparent conductive layer comprises at least one
material selected from a group consisting of indium tin
20 oxide, cadmium tin oxide, antimony tin oxide, zinc oxide,
zinc tin oxide, BeAu, GeAu, and Ni/Au.

19. (original): The light emitting diode of claim 14 wherein
the first and second reaction layers each comprise at least
25 one material selected from a group consisting of SiNx, Ti,
and Cr.

20. (original): The light emitting diode of claim 14 wherein
the transparent adhesive layer comprises at least one
30 material selected from a group consisting of PI, BCB, and
PFCB.

21. (original): The light emitting diode of claim 14 wherein the second stack comprises a second substrate, the first reaction layer being formed on the second substrate.
- 5 22. (original): The light emitting diode of claim 21 wherein the second substrate comprises at least one material selected from a group consisting of SiC, Al₂O₃, glass materials, quartz, GaP, GaAsP, and AlGaAs.

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